

IN THE ABSTRACT OF THE DISCLOSURE:

Please replace the original abstract with the following new abstract:

A plasma processing method using a plasma processing apparatus having a process chamber, a light-receiving part for monitoring a plasma emission in the process chamber, a spectrometer unit for performing a spectrometry on the received plasma emission to convert the same into a multi-channel signal, an arithmetic unit, a database, a determination unit, and an apparatus controller. The method includes the steps of converting the multi-channel signal output from the spectrometer unit into a batch of output signals, finding differences between the output signals and output signals of the preceding batch, and comparing an average value of the differences in one batch, a difference between a maximum and a minimum of the differences in one batch, and a standard deviation of the differences in one batch with a preset threshold.